

# APAC SILICIDE 2010 PROGRAM

(update 2010/6/23)

## July 24

13:00→ 13:20 *Opening address*, Y. Maeda, Chairman, APAC-SILICIDE 2010

### Session I: Nano Silicide: Synthesis, Characterization, and Applications

13:20—14:20 [24-PM-I-1] *Plenary*

Structure, Growth and Electrical Properties of Endotaxial Silicide Nanowires  
P. A. Bennett, *Arizona State Univ., USA*

14:20—15:00 [24-PM-I-3] *Invited*

Synthesis, Properties and Applications of Transition Metal Silicide Nanowires  
J. M. Higgins, R. Ding, P. Carmichael, J. P. DeGrave, and Song. Jin  
*University of Wisconsin-Madison, USA*

### Break 15:00—15:20

15:20—15:40 [24-PM-I-4]

Simple Synthesis of  $ZrO_2/SiO_x$  Core/Shell Nanofibers Using  $ZrSi_2$  with Gallium  
Q. Yang, H. Kukino, <sup>1</sup>M. Tanaka, A. Ishida, and H. Tatsuoka,  
*Shizuoka University, <sup>1</sup>NIMS, Japan*

15:40—16:00 [24-PM-I-5]

$Fe_3Si$  Nanodots Epitaxially Grown on Si(111) Substrates Using Ultrathin  $SiO_2$  Film Technique  
Y. Nakamura, <sup>1</sup>S. Amari, and <sup>1</sup>M. Ichikawa  
*Osaka University, <sup>1</sup>University of Tokyo, Japan*

### 16:10—17:40 Poster Session I

### Session II: Silicide Basics

17:40—18:20 [24-PM-II-1] *Invited*

Preparation of High Purity Metals for Advanced Devices  
Prof. M. Isshiki, *Tohoku University, Japan*

18:20—18:40 [24-PM-II-2]

Magnetization of Bulk  $Mn_{11}Si_{19}$  and  $Mn_4Si_7$  Crystals  
K. Hammura, <sup>1</sup>H. Udono, <sup>2</sup>I. J. Ohsugi, and <sup>1</sup>T. Aono  
*Hitachi Cambridge Lab., Cavendish Lab, UK, <sup>1</sup>Ibaraki University, <sup>2</sup>Salesio Polytechnic, Japan*

18:40—19:00 [24-PM-II-3]

Effect of Deposition Rate and a-Si Precursor on Optical and Magnetic Properties of Iron Films on Silicon Substrates  
<sup>1</sup>A. Goualnik, <sup>1,2</sup>N. Galkin, and <sup>2</sup>V. Ivanov  
<sup>1</sup>*Lab. of Optics and Electrophysics of Nanostructures, Russia*  
<sup>2</sup>*Far Eastern Branch of Russian Academy of Science, Russia*

19:00—19:20 [24-PM-II-4]

Basic Properties of  $Ba_{1-x}Sr_xSi_2$   
*M. Imai, National Institute for Materials Science, Japan*

## **July 25**

### **Session III: Nano-area Characterization**

8:30—9:10 [25-AM-III-1] *Invited*

Crystallographic Characteristics and Fine Structures of Semiconducting Silicides  
G. Shao, *Univ. Bolton, UK*

9:10—9:50 [25-AM-III-2] *Invited*

Advances in Laser Atom Probe and Its Applications to Semiconductor and Insulator Materials  
K. Hono and T. Ohkubo  
*National Institute for Materials Science, Japan*

9:50—10:10 [25-AM-III-3]

Photoabsorption Nano-Spectroscopy for Characterizing of  $\beta$ -FeSi<sub>2</sub> Nanoislands Grown on Si(111) and Si(001):  
Dependence on Substrate Orientation  
N. Naruse, <sup>1</sup>Y. Nakamura, Y. Mera, M. Ichikawa, and K. Maeda  
*University of Tokyo, <sup>1</sup>Osaka University, Japan*

### **Break 10:10—10:30**

### **Session IV: Silicide Spintronics**

10:30—11:10 [25-AM-IV-1] *Invited*

Electrical Spin Injection and Detection in Si Using Ferromagnetic-Silicide Contacts  
K. Hamaya and M. Miyao  
*Kyushu University, Japan*

11:10—11:30 [25-AM-IV-2]

Ion Channeling Study of Epitaxy of Iron Based Heusler Alloy Films on Ge(111)  
<sup>1</sup>T. Ikeda, <sup>2</sup>K. Narumi, <sup>2</sup>Y. Terai, <sup>3</sup>K. Hamaya, <sup>3</sup>T. Sadoh, <sup>3</sup>M. Miyao, and <sup>1,5</sup>Y. Maeda  
*<sup>1</sup>Kyoto University, <sup>2</sup>TIARA JAEA, <sup>3</sup>Osaka University, <sup>4</sup>Kyushu University, <sup>5</sup>ARSC JAEA, Japan*

11:30—11:50 [25-AM-IV-3]

Fabrication of Fe<sub>3</sub>Si/CaF<sub>2</sub> Heterostructures Ferromagnetic Resonant Tunneling Diode by Selected-Area  
Molecular Beam Epitaxy  
K. Sadakuni-Makabe, M. Suzuno, K. Harada, <sup>1</sup>H. Akinaga, and T. Suemasu  
*University of Tsukuba, Japan, <sup>1</sup>AIST, Tsukuba, Japan*

11:50—12:10 [25-AM-IV-4]

Significance of the Interface Regarding Magnetic Properties of Mn-Nanosilicide in Silicon  
Y. Ono, <sup>1</sup>Y. Miyazaki, <sup>1</sup>S. Yabuuchi, H. Kageshima, M. Nagase, A. Fujiwara, and <sup>1</sup>E. Ota  
*NTT Basic Research Lab., Japan, <sup>1</sup>Keio University*

### **Lunch Break 12:10—13:30**

### **Session V: Silicide Devices and Optical Properties**

13:30—14:10 [25-PM-V-1] *Invited*

New Semiconducting Silicides Assembled from Transition-Metal-Encapsulating Si Clusters  
T. Kanayama, N. Uchida, and T. Miyazaki  
*National Institute of Advanced Industrial Science and Technology, Japan*

14:10—14:30 [25-PM-V-2]

Iron Silicide Studies Towards Photonics  
Y. Maeda  
*Kyoto University, Japan*

14:30—14:50 [25-PM-V-3]

Growth, Structure and Luminescence Properties of Multilayer Si/ $\beta$ -FeSi<sub>2</sub> NCs/Si/Si Nanoheterostructures  
N. G. Galkin, E. A. Chusovitin, <sup>1</sup>T. S. Shamirsaev, <sup>1</sup>A. K. Gutakovski, <sup>1</sup>A. V. Latyshev  
*Far Eastern Branch of Russian Academy of Science, Russia*  
<sup>1</sup>*Inst. Semiconductor Physics and Siberian Branch of Russian Academy of Science*

**Break 14:50—15:10**

15:10—15:30 [25-PM-V-4]

Antireflection Coatings with FeSi<sub>2</sub> Layer-I: Application to Low-Reflective Wire-Grid Polarizers  
M. Suzuki, <sup>1</sup>A. Takada, <sup>1</sup>T. Yamada, <sup>1</sup>T. Hayasaka, <sup>1</sup>K. Sasaki, <sup>1</sup>E. Takahashi, and <sup>1</sup>S. Kumagai  
*Kyoto University, <sup>1</sup>Sony Chemical & Information Device Corporation*

15:30—15:50 [25-PM-V-5]

Band-gap Modifications of  $\beta$ -FeSi<sub>2</sub> Epitaxial Films by Lattice Deformations  
Y. Terai, K. Noda, K. Yoneda, <sup>1</sup>H. Uono, <sup>2</sup>Y. Maeda, and Y. Fujiwara  
*Osaka University, <sup>1</sup>Ibaraki University, <sup>2</sup>Kyoto University*

**16:00—17:30 Poster Session II**

18:30—20:30 **Banquet Ushiku Chateau**

<http://www.ch-kamiya.jp/>

## **July 26**

### **Session VI: Silicide Green Technologies**

8:30—9:10 [26-AM-VI-1] *Invited*

Metal Induced Crystallization of Amorphous Silicon for Photovoltaic Solar Cells  
D. Van Gestel, I. Gordon, and J. Poortmans  
*IMEC, Belgium*

9:10—9:30 [26-AM-VI-2]

Photovoltaic Properties of n-Type  $\beta$ -FeSi<sub>2</sub>/Intrinsic Si/p-Type Si Heterojunctions  
T. Yoshitake, K. Nomoto, I. Shota, N. Promros, and <sup>1</sup>M. Shaban  
*Kyushu University, Japan, <sup>1</sup>South Valley University, Egypt*

9:30—9:50 [26-AM-VI-3]

Photoresponse Properties of BaSi<sub>2</sub> Epitaxial Films Grown on the Tunnel Junction for High-Efficiency Thin-Film Solar Cells  
T. Saito, K. Toh, A. Okada, and T. Suemasu  
*University of Tsukuba, Japan*

9:50—10:10 [26-AM-VI-4]

Computational Design of High Efficient FeSi<sub>2</sub> Thin-Film Solar Cells  
Y. Gao, H.W. Liu, and <sup>1</sup>G. Shao  
*Hubei University, P. R. China, <sup>1</sup>University of Bolton, UK*

10:10—10:30 [26-AM-VI-5]

Metalorganic Chemical Vapor Deposition of  $\beta$ -FeSi<sub>2</sub> on  $\beta$ -FeSi<sub>2</sub> Seed Crystals formed on Si substrates  
M. Suzuno, K. Akutsu, H. Kawakami, <sup>1</sup>K. Akiyama, and T. Suemasu  
*University of Tsukuba, <sup>1</sup>Kanagawa Ind. Tech. Center, Japan*

### **Break 10:30-10:50**

10:50—11:10 [26-AM-VI-6]

Thermoelectric Properties and Power Generation Characteristics Sintered n-type Mg<sub>2</sub>Si  
T. Sakamoto, T. Iida, N. Fukushima, Y. Honda, M. Tada, <sup>1</sup>Y. Taguchi, <sup>2</sup>Y. Mito, H. Taguchi, and Y. Takanashi  
*Tokyo University of Science, <sup>1</sup>Union Material Inc., <sup>2</sup>Showa KDE Co., Ltd., Japan*

11:10—11:30 [26-AM-VI-7]

Preparation and Thermoelectrical Properties of Higher Manganese Silicide Bulk Prepared From a Mn Compact Using a Na-Si Melt  
T. Yamada, Y. Miyazaki, and H. Yamane  
*Tohoku University, Japan*

11:30—11:50 [26-AM-VI-8]

Growth of Homogeneous Mg<sub>2</sub>Si<sub>1-x</sub>Ge<sub>x</sub> Crystals for Thermoelectric Application  
Y. Hayakawa, M. Arivanandhan, Y. Saito, T. Koyama, Y. Momose, H. Ikeda, A. Tanaka, Cuilian Wen, Y. Kubota, T. Nakamura, Dinesh Kumar Aswal, <sup>1</sup>S. Bhattachary, <sup>2</sup>Y. Inatomi, and H. Tatsuoka  
*Shizuoka University, Japan, <sup>1</sup>Bhabha Atomic Research Center, India, <sup>2</sup>Japan Aerospace Exploration Agency, Japan*

Closing 11:50→12:00